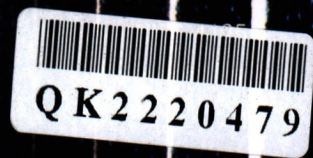


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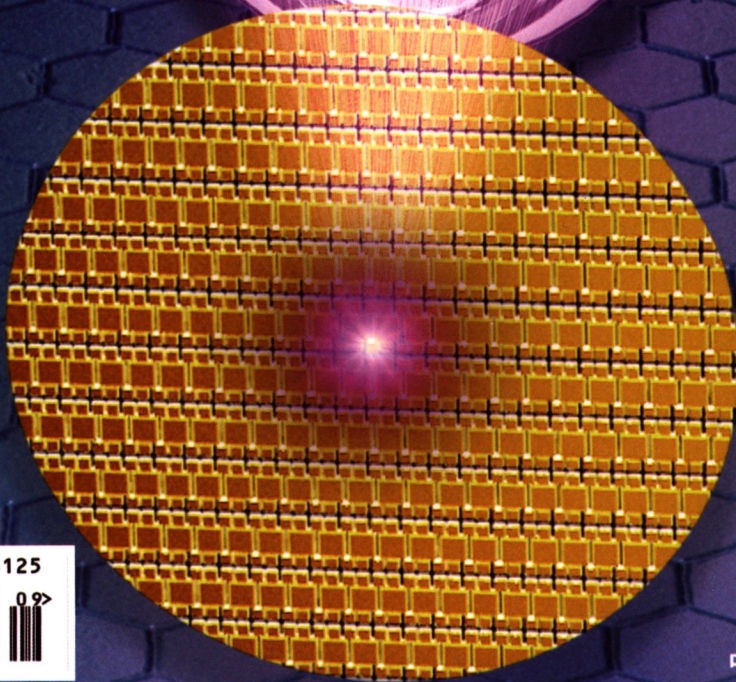
第 59 卷
第 9 期

Laser & Optoelectronics Progress

[总第716期]

2022.5 (上)

专题 | 光刻技术



计算光刻

DOI: 10.3788/LOP202259.0922001

ISSN 1006-4125



万方数据

中国科学院上海光学精密机械研究所 主办

激光与光电子学进展

第 59 卷 第 9 期 2022 年 5 月 10 日

(总第 716 期)

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封面解读

计衡微纳间,算验万核前。
光行精妙路,刻就芯片圆。

封底解读

封面形象示意了极紫外(EUV)光刻机光源的基本原理:预、主脉冲分别与靶材作用产生极紫外光,后者被收集镜收集,经过光谱纯化传输至光刻系统以曝光晶圆。EUV光源是EUV光刻机中最核心的分系统之一,是下一代大规模工业化量产工艺制程的必备技术。

内封面解读(封二)

封面包含光刻机运动台和运动控制两大部分。以光刻机工件台为背景,光刻机运动台系统是光机电高度一体化的产物,而工件台是运动台系统的典型代表。要实现超精密光刻工艺,针对运动台的先进控制必不可少。其中光刻机运动台的控制框图,表现出包含多自由度解耦、前馈控制和反馈控制的系统控制架构。

内封面解读(封三)

封面中光刻胶分子从芯片的光刻焦点向外飞出,表示它们都是光刻过程中必不可少的分子。极紫外光刻胶是实现最先进芯片制造的关键材料,对极紫外光刻的效果影响巨大。

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专题 | 光刻技术

极紫外光源

DOI: 10.3788/LOP202259.0922002



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